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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Te Application of:

Faquir C. JAIN and Fotios PAPADIMITRAKOLPOULOS

Art unit: 1774

Serial No. 09/547,415

Examiner: D. GARRETT

Filed: April 11, 2000

For: FULL COLOR DISPLAY STRUCTURE USING CNC THIN FILM

PRRELIMINARY AMENDMENT (clear copy)

Commissioner of Patents Washington, D.C. 20231

Sir:

Please amend the original patent application as follows:

IN THE CLAIMS:

Please rewrite claim 2 as follows:

--2. An EL device of claim 1, wherein the thin wide energy gap semiconductor layer over the said CNC layer is undoped --

Please delete claim 4

Please amend claim 5 as follows:

--5. An EL device of claim 1, wherein said CNC layer is sandwiched between compatible wide energy gap semiconductor layers selected from the group of semiconductors consisting of Zn<sub>a</sub>Mg<sub>1-a</sub>Se, Zn<sub>a</sub>Mg<sub>1-a</sub>S, Zn<sub>a</sub>Mg<sub>1-a</sub>S<sub>b</sub>Se<sub>1-b</sub>, ZnaBe<sub>1-a</sub>S<sub>b</sub>Se<sub>1-b</sub>, AlcGa<sub>1-c</sub>N, and AlInN.--

Please amend claim 8 as follows:

--8. An EL device of claim 1, wherein the layer comprising CNC further\_comprises multiple layers of CNCs sandwiched between epitaxially grown thin film layers of wide energy gap semiconductors. --

Please cancel claims 9.

Please rewrite claim 11 as follows:

--11. An device EL device as described in claim 1, wherein said first p-doped Si layer is substituted by a transparent ITO, forming the bottom electrodes.--

Please rewrite claims 13-16 as follows:

--13. An EL device of claim 1, wherein the *p*-doped wide energy gap semiconductor layer underneath the said CNC layer is replaced by a dielectric layer.

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